



SHEET ____ of ____

INFORMATION DISCLOSURE CITATION PTO-1449	Att'y. Docket No. NMTC-0770	Serial No. 10/020114
	Applicant MACLEAN, Kevin	Group Technology Center 2100
	Filing Date 3/15/2002	2123

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AS	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
	6,339,836 B1	1/15/2002	Eisenhofer, et al.	716	5	8/24/1998
	6,453,452 B1	9/17/2002	Chang, et al.	716	8	9/16/1998
	6,453,457 B1	9/17/2002	Pierrat, et al.	716	19	9/29/2000
	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002
	2002/0152449 A1	10/17/2002	Lin	716	17	4/13/2001
	2002/0152454 A1	10/17/2002	Cote, et al.	716	21	6/7/2002

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SD	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.
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	Anonymous, "Parameterization For Full Shape And Rule Dependent Dissection", IPCOM000009587D, September 4, 2002 (9 pages). <i>late past filing date</i>

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
✓	5,182,718	1/26/1993	Harafuji, et al.	364	490	3/29/1990
	5,432,714	7/11/1995	Chung, et al.	364	525	9/2/1994
	5,533,148	7/2/1996	Soyah, et al.	382	240	9/30/1993
	5,538,815	7/23/1996	Oi, et al.	430	5	9/14/1993
	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
	5,657,235	8/12/1997	Liebmann, et al.	364	474.24	5/3/1995
	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
	5,825,647	10/20/1998	Tsudaka	364	167.03	3/12/1996
	5,885,734	3/23/1999	Pierrat, et al.	430	5	8/15/1996
	5,991,006	11/23/0199	Tsudaka	355	53	10/27/1997
	6,009,250	12/28/1999	Ho, et al.	395	500.06	9/30/1997
	6,009,251	12/28/1999	Ho, et al.	395	500.06	9/30/1997
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	6,081,658	6/27/2000	Rieger, et al.	395	500.22	12/31/1997
	6,289,499	9/11/2001	Rieger, et al.	716	21	1/7/2000
	6,243,855 B1	6/5/2001	Kobayashi, et al.	716	19	9/29/1998
	6,249,597 B1	6/19/2001	Tsudaka	382	144	12/17/1998
	6,370,679 B1	4/9/2002	Chang, et al.	716	19	9/16/1998
	2002/0010904 A1	1/24/2002	Ayres	716	19	7/23/2001

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<i>SP</i>	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
	WO 00/67074 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 02/29491 A1	4/11/2002	WO			<input type="checkbox"/>	<input type="checkbox"/>
	GB 2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>
	WO 97/38381	10/16/1997	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14636 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14637 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14638 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

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